

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :
Tomohiro OKUMURA et al. : Attn: APPLICATION BRANCH
Serial No. NEW : Docket No. 2001_1089A
Filed August 1, 2001 :

PLASMA PROCESSING METHOD AND
APPARATUS THEREOF

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEE FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975.

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents,
Washington, DC 20231

Sir:

Prior to initial examination of the above-identified new patent application,
kindly amend the application as follows:

IN THE CLAIMS:

Kindly amend claims 29 and 37 as follows:

29.(Amended)

A plasma processing apparatus as defined in claim 27, wherein
the dielectric tube is disposed such that (it) covers an edge of a hole of the metal body or
(the facing electrode).

37.(Amended)

A plasma processing apparatus as defined in claim 28, wherein
the dielectric tube is disposed such that (it) covers an edge of a hole of the metal body or
(the facing electrode).